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10/624,350**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Use several sheets if necessary)

APPLICANT

Aaron Scott Lukas, et al.

(37 CFR 1.98(b))

FILING DATE

7/21/03

GROUP

1762**U.S. PATENT DOCUMENTS**

EXAM NUMBER	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5 4 5 4 9 1 5	10/3/1995	J. S. Shor, et al. ✓	204	129.3	9/1/1993
	6 0 4 2 9 9 4	3/28/2000	J. Yang, et al. ✓	430	296	1/8/1999
	6 0 5 4 2 0 6	4/25/2000	T. W. Mountsier ✓	428	312.8	6/22/1998
	6 2 3 8 7 5 1	5/29/2001	T. W. Mountsier ✓	427	574	3/16/2000
	6 2 8 4 0 5 0	9/4/2001	J. Shi, et al. ✓	118	715	5/18/1998
	6 3 1 2 7 9 3	11/6/2001	A. Grill, et al. ✓	428	312.6	5/26/1999
	6 4 7 5 9 3 0	11/5/2002	K. H. Junker, et al. ✓	438	787	1/31/2000
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	0 0 3 2 3 0 0	2/13/2003	C. Waldfried, et al. ✓	438	725	5/14/2001
	0 0 5 4 1 1 5	3/20/2003	R. Albano, et al. ✓	427	487	9/14/2001

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
EP 1 0 3 7 2 7 5	Sept-2000	Europe	Maeda et al		YES NO
WO 0 0 0 2 2 4 1	Jan 2000	World	PCF		X
WO 0 2 0 7 1 9 1	Jan 2003	World	PCF		X
WO 02 0 6 5 5 3 4	Aug 2002	World	PCF		X

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesoporous Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light, Chem. Mater. 2000, 12, 3842-3847. *no month*M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes, Chem Mater. 2000, 12, 1591-1596. *no month, but published on Web May 2000*

A. Hozumi, et al., "Micropatterned Silica Films with Ordered Nanopores Fabricated through Photocalcination, National Institute of Advanced Industrial Science & Technology, Volume 1, Number 8, August 2001.

T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films, Chem Mater. 2000, 12, 3879-3884. *no month, but pub on web. Dec. 2000*Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173. *no month*C. Waldfried, et al., "Single Water RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228. *no month*

EXAMINER

Michael P. Gallett

DATE CONSIDERED

9/15/05

EXAMINER: Initial citation considered. Draw line through citation if not in conf rmanc and n t consid red. Includ copy of this form with next c mmunication t applicant.